

Electronic Supplementary Information

Novel chemical route for atomic layer deposition of MoS₂ thin film on SiO₂/Si substrate

*Zhenyu Jin, Seokhee Shin, Do Hyun Kwon, Seung-Joo Han and Yo-Sep Min**

Department of Chemical Engineering, Konkuk University, 120 Neungdong-Ro, Gwangjin-Gu, Seoul 143-701, Korea

*E-mail: ysmin@konkuk.ac.kr

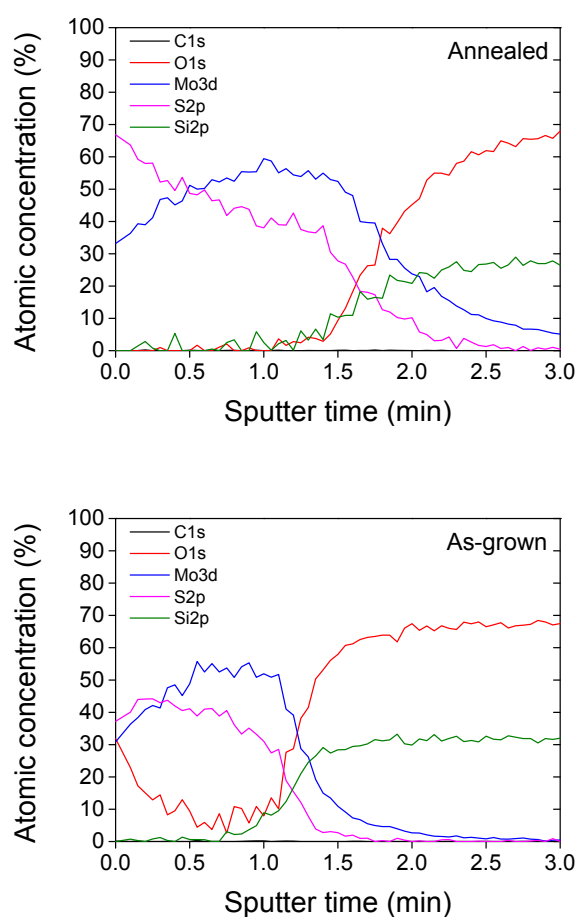


Figure S1. XPS depth profiles of the as-grown and the annealed MoS₂ thin films on SiO₂/Si.

Both films were sputtered by 2 keV Ar⁺ for the depth profiling.